

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : Natl. Phase of PCT/JP2003/011137  
Applicant(s) : Mitsuru UEDA *et al.*  
Filed : herewith  
TC/A.U. :  
Examiner :  
Docket No. : 28955.1048  
Customer No. : 27890  
Title : PHOTORESIST BASE MATERIAL, METHOD FOR  
PURIFICATION THEREOF, AND PHOTORESIST COMPOSITIONS

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**PRELIMINARY AMENDMENT**

Sir:

Prior to examination of the instant application, please amend the above-identified application as follows:

**Amendments to the Claims** to be entered for consideration by the Examiner prior to examination are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 11 of this paper.